

US DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE

APPLICANT: MARTIN RICHARDSON
FOR: EUV, XUV, AND X-RAY WAVELENGTH SOURCES CREATED FROM LASER PLASMA
PRODUCED FROM LIQUID METAL SOLUTIONS, AND NANO-SIZE PARTICLES IN SOLUTIONS

LIST OF ART CITED BY APPLICANT

U.S. PATENT DOCUMENTS

EXAMINER	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
CT ↓	AA	4,024,400	05/17/77	Blytas et al.	250	432	05/13/76
	AB	4,328,464	05/04/82	Pivirotto	330	4.3	02/07/80
	AC	4,700,371	10/13/87	Forsyth et al.	378	34	11/08/84
	AD	4,723,262	02/02/88	Noda et al.	378	119	12/26/85
	AE	4,866,517	09/12/89	Mochizuke et al.	378	119	09/10/87
	AF	4,953,191	08/28/90	Smither et al.	378	143	07/24/89
	AG	5,052,034	09/24/91	Schuster	378	121	10/29/90
	AH	5,126,755	06/30/92	Sharpe et al.	346	75	03/26/91
	AI	5,142,297	08/25/92	Eijkman et al.	346	1.1	03/26/90
	AJ	5,148,462	09/15/92	Spitsyn et al.	378	143	04/08/91
	AK	5,151,928	09/29/92	Hirose	378	119	08/20/91
	AL	5,243,638	09/07/93	Wang et al.	378	119	03/10/92
	AM	5,257,303	10/26/93	Das Gupta	378	85	08/03/92
	AN	5,317,574	05/31/94	Wang	372	5	12/31/92
	AO	5,459,771	10/17/95	Richardson et al.	378	119	04/01/94
	AP	5,577,091	11/19/96	Richardson et al.	378	119	01/13/95
	AQ	5,577,092	11/19/96	Kublak et al.	378	119	11/19/96
	AR	5,991,360	11/23/99	Matsui et al.	378	119	02/03/98
	AS	6,002,744	12/14/99	Hertz et al.	378	119	10/21/98
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AU	6,185,277	02/06/01	Harding	378	143	05/07/99	
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FOREIGN PATENT DOCUMENTS

FA	JA57/41167	March 1982	JAPAN
FB	JA0267895	11/90	Iwamatsu

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

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OA T.P. Donaldson, *SOFT X-RAY SPECTROSCOPY OF LASER-PRODUCED PLASMAS WITH A CONVEX MICA CRYSTAL SPECTROMETER*, X-Ray Astronomy Group, Vol. 9, P. 1645-1655, 1 March 1976OB T. Mochizuki, *SOFT X-RAY OPTICS AND TECHNOLOGY*, Proceedings Of SPIE-The International Society For Optical Engineering, Vol. 733, P. 23-27, December 1986OC Martin Richardson, *LASER PLASMA SOURCE FOR X-RAY PROJECTION LITHOGRAPHY*, Laser-Induced Damage In Optical Materials, Vol. 1848, P. 483-500, 1992OD W.T. Silfvast, *LASER-PRODUCED PLASMAS FOR X-RAY PROJECTION LITHOGRAPHY*, American Vacuum Society, P. 3126-3133, 4 August 1992OE F. Jin, *MASS LIMITED PLASMA CYROGENIC TARGET FOR 13NM POINT X-RAY SOURCES FOR LITHOGRAPHY*, Application of Laser Plasma Radiation, Vol. 2015, P. 1-9, August 1993

Courtney Thomas : 01.02.03